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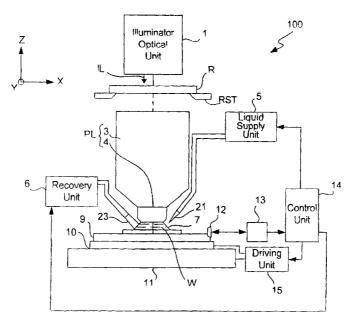
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[Continued on next page]

(54) Title: LIQUID JET AND RECOVERY SYSTEM FOR IMMERSION LITHOGRAPHY



(57) Abstract: A liquid jet and recovery system for an immersion lithography apparatus (100) has arrays of nozzles arranged to have their openings located proximal to an exposure region through which an image pattern is projected on a workpiece (W) such as a wafer. These nozzles are each adapted to serve selectively either as a source nozzle (21) for supplying a fluid (7) into the exposure region or as a recovery nozzle (23) for recovering the fluid from the exposure region. A fluid controlling device (14) functions to cause nozzles on selected one or more sides of the exposure region to serve as source nozzles and those on selected one or more of the remaining sides to serve as recovery nozzles such that a desired flow pattern can be established for the convenience of immersion lithography.



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TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

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B. FIELDS SEARCHED				
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Documentation searched other than minimum documentation to the extent that such documents are included in the fields searched				
Electronic data base consulted during the international search (name of data base and, where practicable, search terms used) Please See Continuation Sheet				
C. DOCUMENTS CONSIDERED TO BE RELEVANT				
X WO99/49504 A1 (FUKAMI ET AL) 30 September and 6	WO99/49504 A1 (FUKAMI ET AL) 30 September 1999 (30.09.1999) see figures 1-3 and 6			
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A DD 221 563 A1 (PFORR ET AL) 24 April 1985	DD 221 563 A1 (PFORR ET AL) 24 April 1985 (24.04.1985) see figures 1 and 3			
A US 5,825,043 A (SUWA) 20 October 1998 (20.1)	US 5,825,043 A (SUWA) 20 October 1998 (20.10.1998) see figure 9			
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04 February 2005 (04.02.2005) Name and mailing address of the ISA/US	Name and mailing address of the ISA/IIS Authorized officer hands and mailing address of the ISA/IIS			
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Search Terms: immersion and nozzle\$4 and (lithograph\$4 or wafer or substrate)		